

## ABSTRACT OF THE DISCLOSURE

A scanning exposure apparatus includes an illumination optical system for defining an illumination region, having a slit-like section, on an original with use of laser light from a continuous emission type excimer laser, and a driving device for relatively, scanningly moving an original and a substrate relative to the illumination region. The illumination optical system includes a scanning optical system for scanning a pupil plane of the illumination system with the laser light to produce a secondary light source thereon, such that the illumination region is defined by light from the secondary light source. When the width of the illumination region is  $W$  (mm), the scan speed of at least one of the original and the substrate is  $V$  (mm/sec), and the time necessary for defining the secondary light source once is  $T$  (sec), a relation  $W/V = nT$  is satisfied, in which  $n$  is an integer.